



NOTES:

1. MATERIAL: UVFS
2. COATING (S1) : HIGH ENERGY LASER LINE COATING  
 $R_s, R_p > 99\% @ 532 \text{ nm}, 0^\circ - 45^\circ \text{ AOI}$
3. CLEAR APERTURE (S1) :  $> 90\%$  (CA)
4. SURFACE QUALITY (S1) : 20/10 (S/D)
5. SURFACE FLATNESS (S1) :  $\lambda / 10 @ 633 \text{ nm}$
6. PARALLELISM (S1, S2) :  $< 3 \text{ arcmin}$
7. CHAMFER:  $< 0.2 \text{ mm}, 45^\circ$
8. BACK SURFACE (S2) : FINE GROUND

DRAWING PROJECTION			<b>LBTEK</b>			
	NAME	DATE				
DRAWN	Lynne	JAN./12th/24	HIGH ENERGY LASER LINE MIRROR $\text{Ø } 50.8 \text{ mm} \times 12 \text{ mm}, 532 \text{ nm}$			
APPROVAL	CWZ	JAN./12th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	53.57g	3:2	A